

In place of PTO-1449 Form INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)	U. S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		Complete if Known		
	Application Number				
	Filing Date		Herewith		
	Applicant(s)		Chien-Chao Huang		
	Art Unit				
Examiner Name					
SHEET 1 OF 1		Attorney Docket Number		24061.150 (TSMC2003-0964)	

U. S. PATENT DOCUMENTS				
Examiner's Initials	Cite No.	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document
JD	AA	6,583,000	06-24-2003	Hsu et al.
TD	AB	6,600,170	07-29-2003	Xiang

FOREIGN PATENT DOCUMENTS					
Examiner's Initials	Cite No.	Foreign Patent Document (Country Code - Number - Kind)	Publication Date MM-DD-YYYY	Patentee or Applicant of Cited Document	Translation Y/N

OTHER PRIOR ART		
Examiner's Initials	Cite No.	Include name of the author, (in CAPITAL LETTERS) title of the article, title of the item, date, page(s), volume, issue, number(s), publisher, city/country where published
JD	AC	Y. C. YEO et al., "Enhanced Performance in Sub-100 nm CMOSFETs using Strained Epitaxial Silicon-Germanium", IEDM Technical Digest, December 10-13, 2000, pgs. 753-756, IEEE.
TD	AD	C. R. SELVAKUMAR et al., "Sige-Channel NMOSFET by Germanium Implantation", IEEE Electron Device Letters, 1991, Vol/Issue 12/8 August, pages 444-446, IEEE.
TD	AE	Y. H. Wu et al., "High Temperature Formed Sige P-Mosfets With Good Device Characteristics", IEEE Electron Device Letters, 2000, Vol./Issue 21/7 pages 350-352, IEEE.
TD	AF	D. K. Nayak et al., "High-Mobility Strained-Si P-Mosefets, IEEE Transactions on Electron Device, 1996, Vol./Issue 43/10/Oct, pages 1709-1716, IEEE
TD	AG	Xiang Lu et al., "SiGe and SiGeC Surface Alloy Formation Using High-dose Implantation and Solid Phase Epitaxy", International Conference on Ion Implantation Technology, 1997, pages 686 - EOA, IEEE.

Examiner Signature		Date Considered	10/25/05
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include a copy of this form with next communication to applicant.